

FIG. 1

2/18

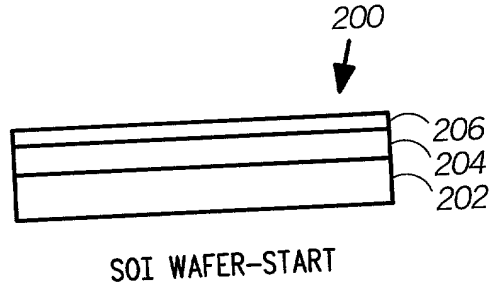


FIG. 2

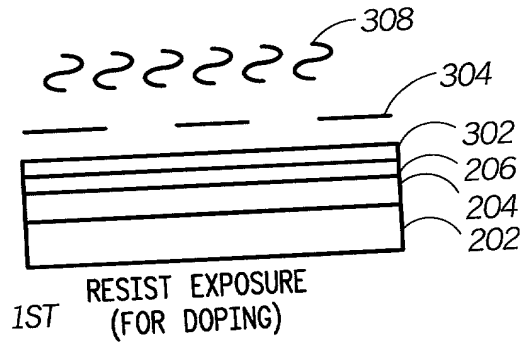


FIG. 3

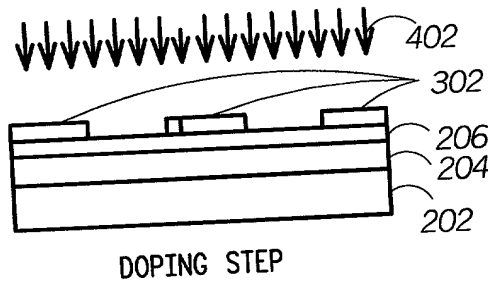


FIG. 4

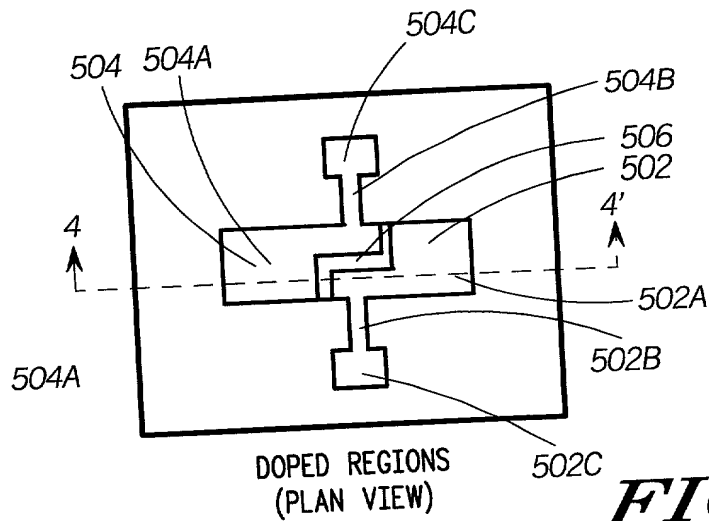


FIG. 5

3/18

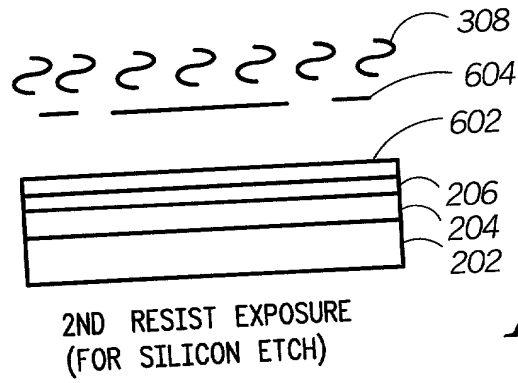


FIG. 6

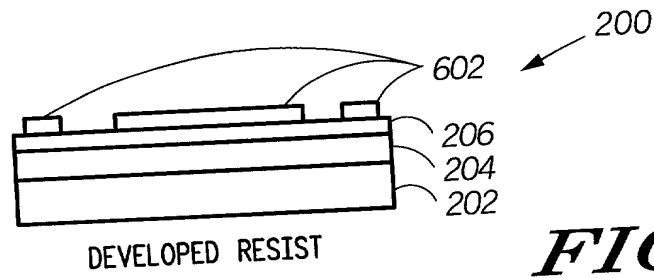


FIG. 7

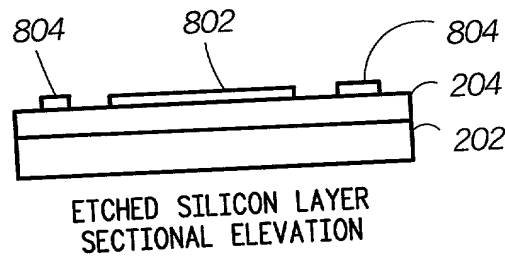


FIG. 8

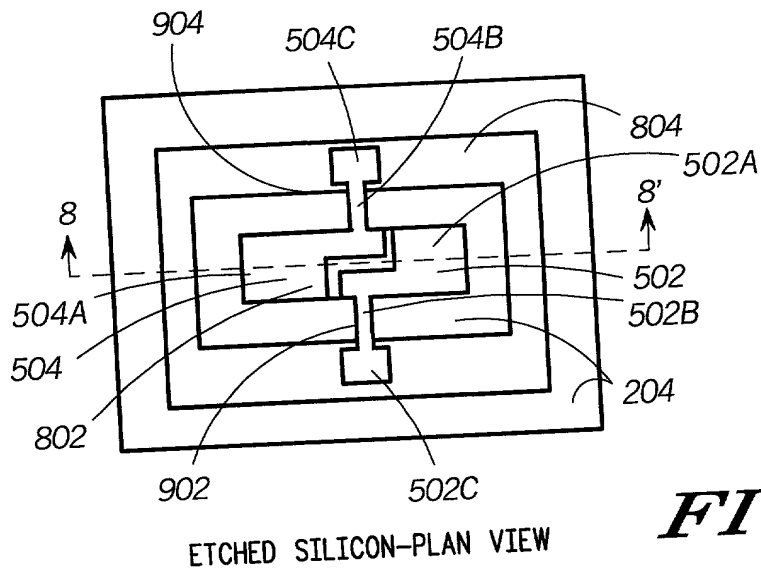
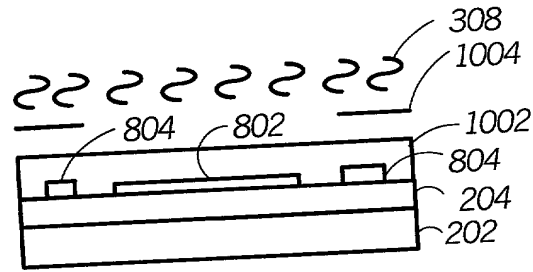


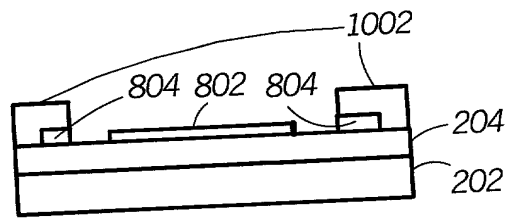
FIG. 9

4/18



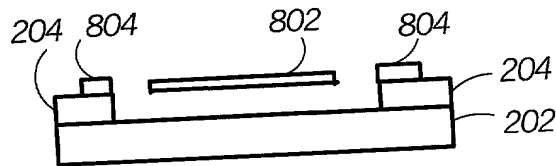
3RD RESIST EXPOSURE
(FOR SI02 ETCH)

FIG. 10



DEVELOPED RESIST

FIG. 11



AFTER SI02 ETCH

FIG. 12





7/18

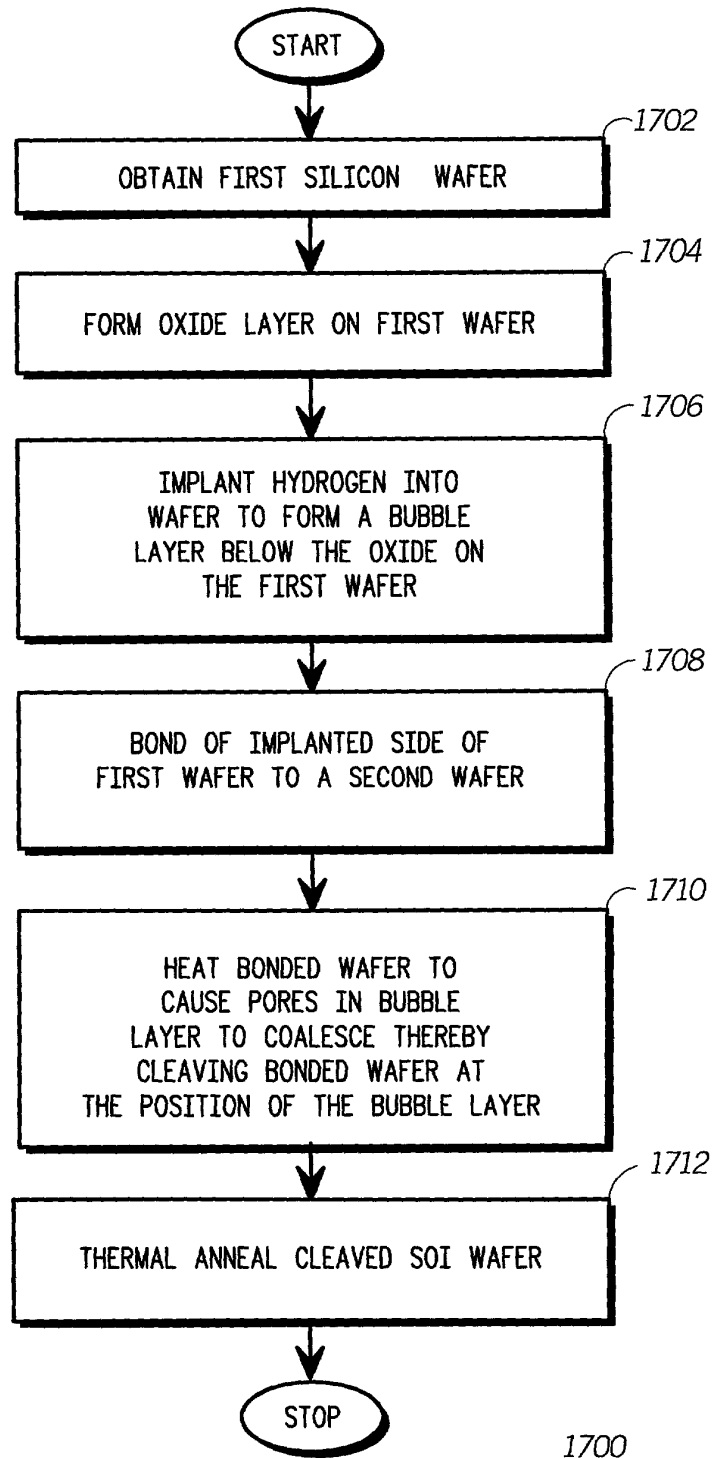


FIG. 17

8/18

FIG. 18

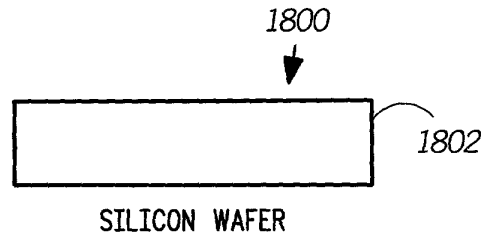


FIG. 19

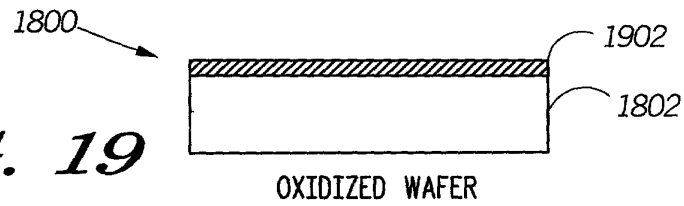


FIG. 20

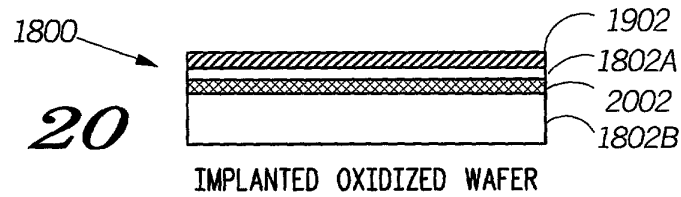


FIG. 21

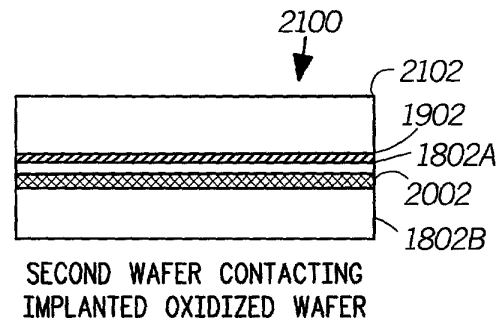
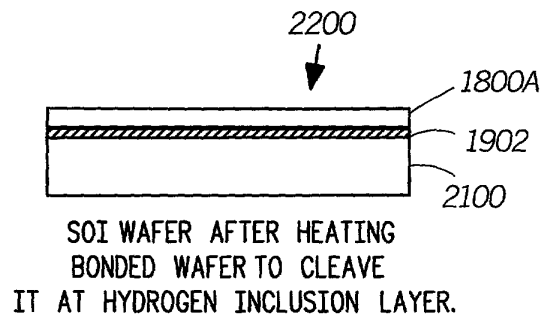


FIG. 22



9/18

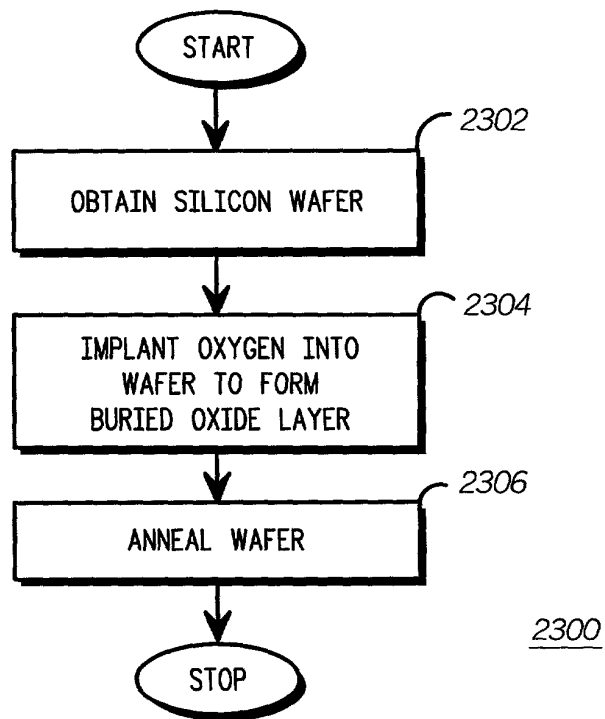


FIG. 23

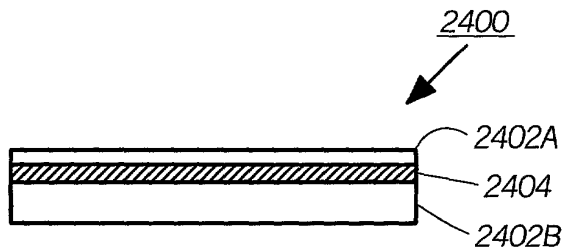
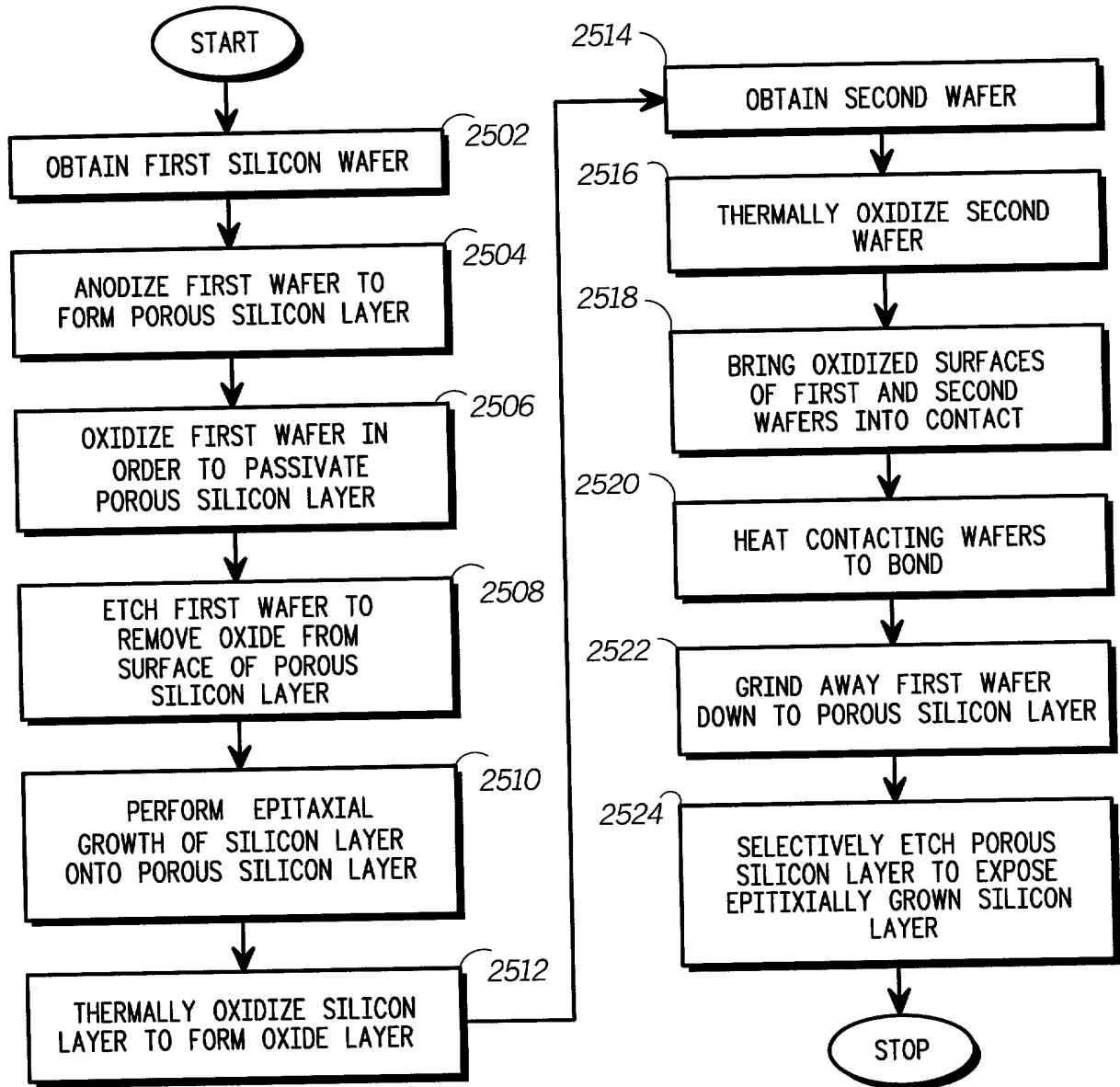


FIG. 24

10/18



2500

FIG. 25

11/18

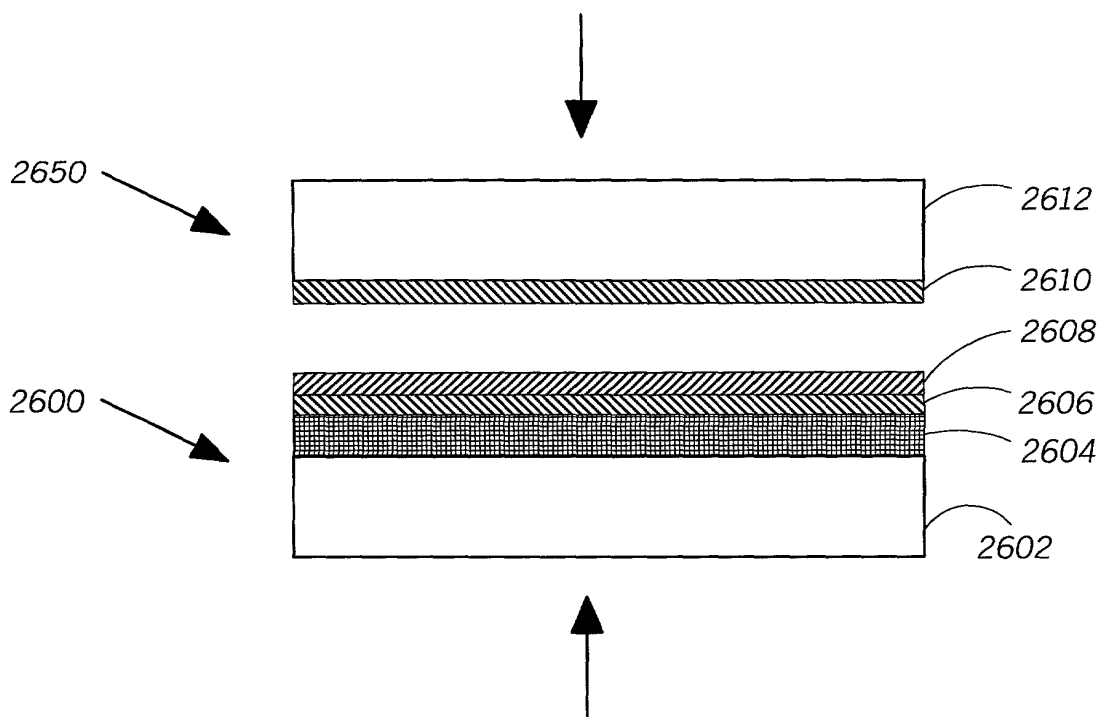


FIG. 26

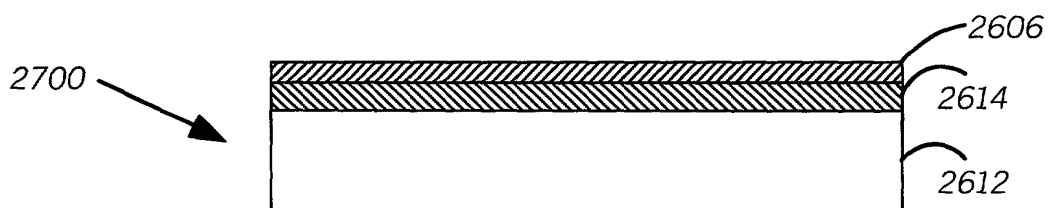


FIG. 27

12/18

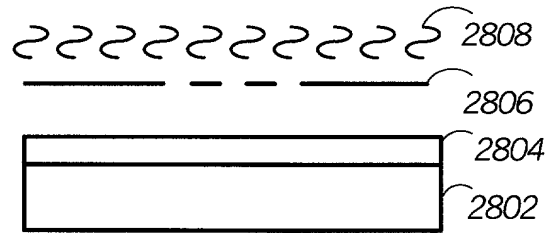


FIG. 28

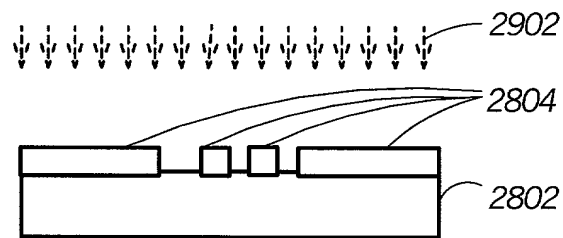


FIG. 29

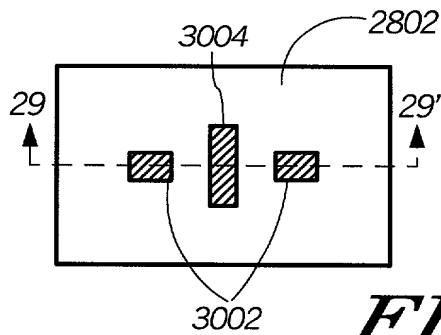


FIG. 30

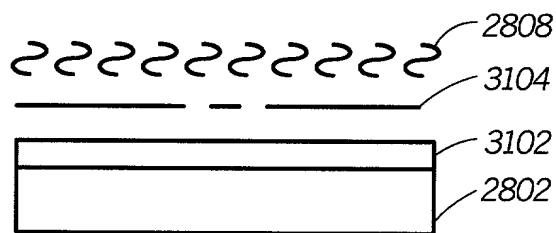


FIG. 31

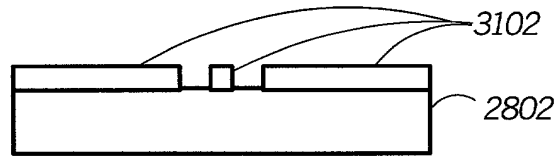


FIG. 32

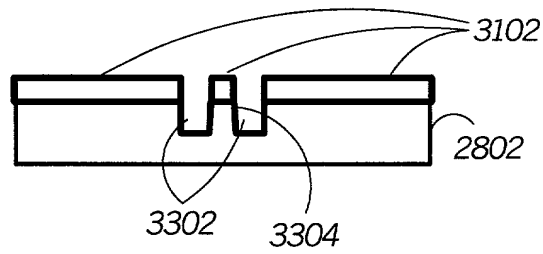


FIG. 33

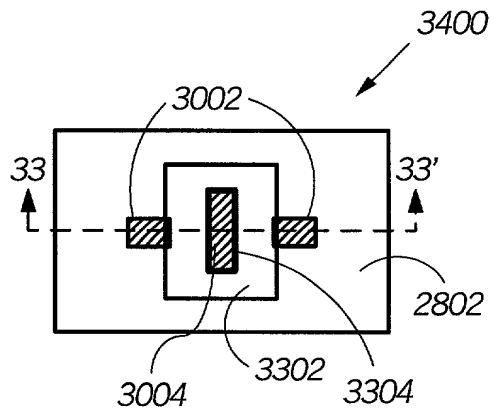


FIG. 34

14/18

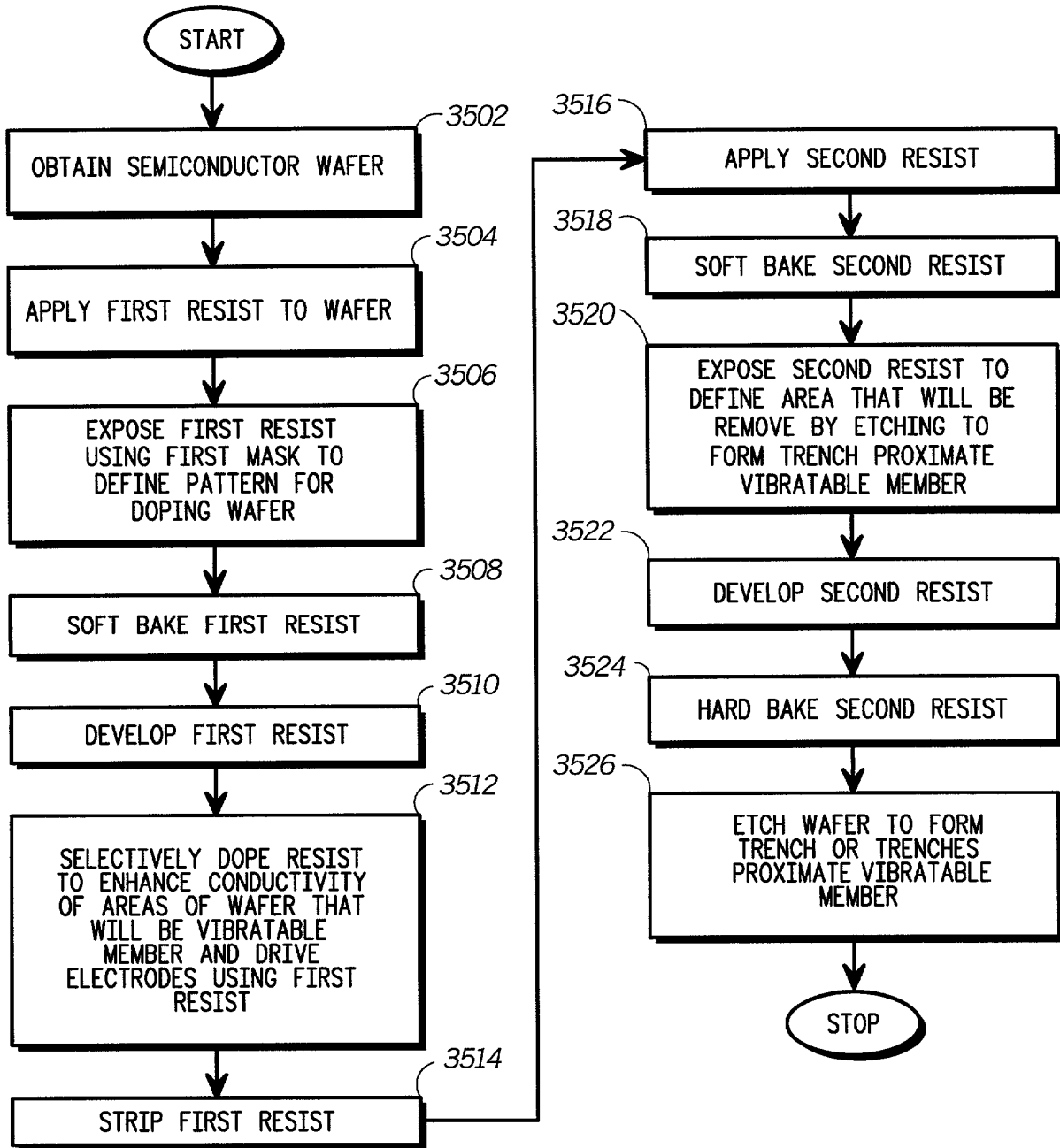


FIG. 35

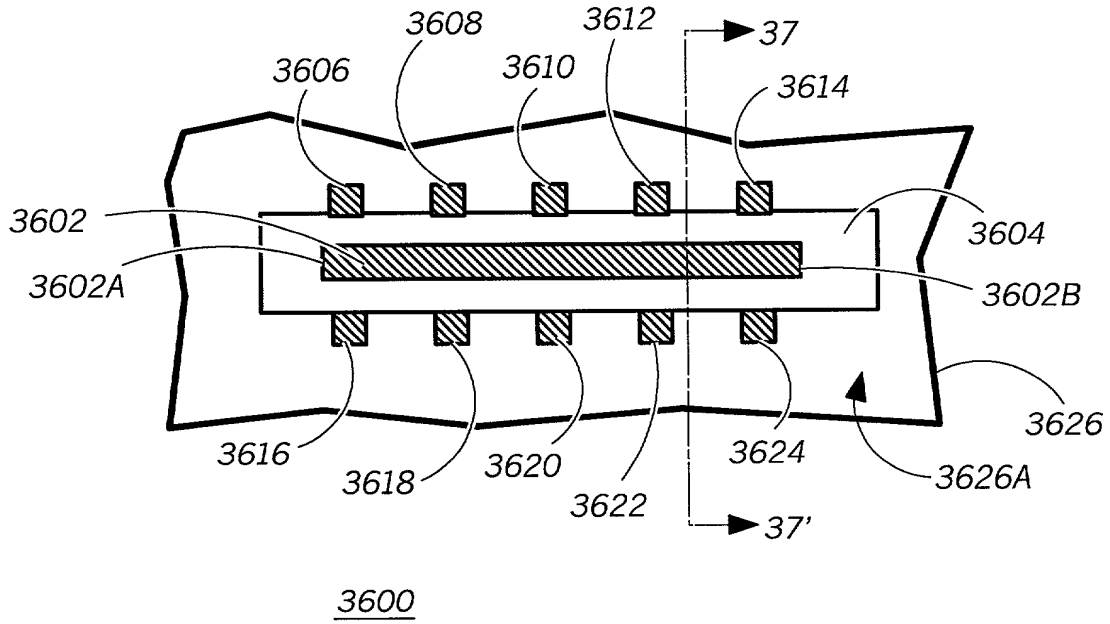


FIG. 36

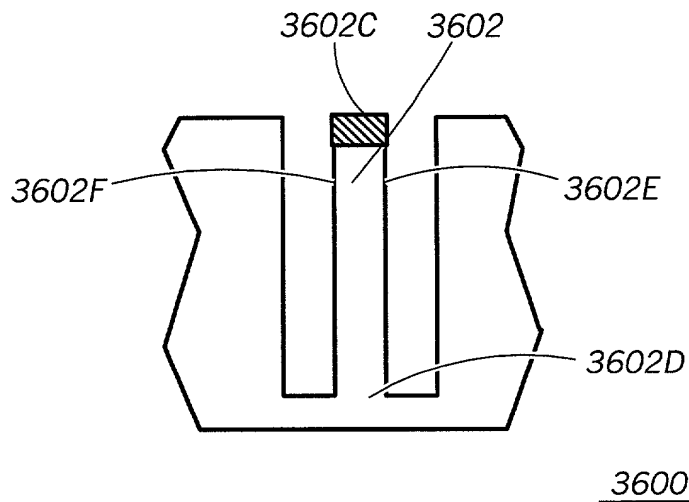


FIG. 37

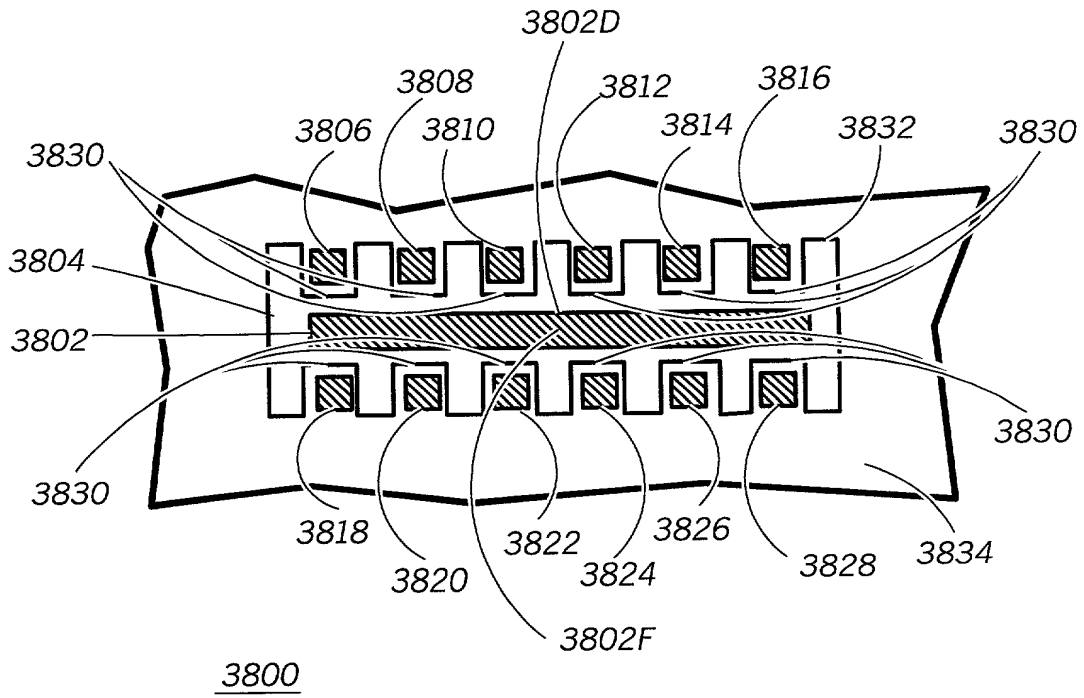


FIG. 38

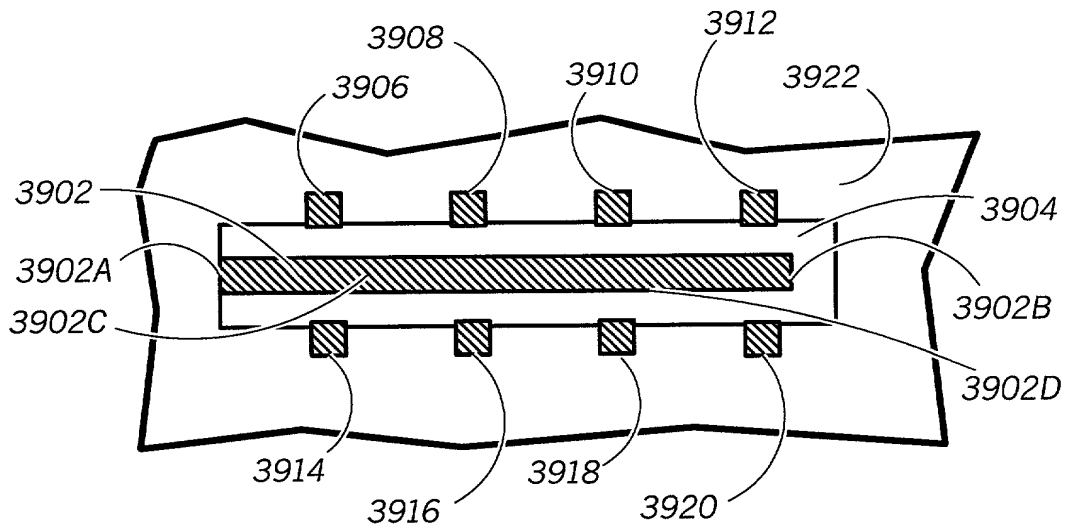


FIG. 39

17/18

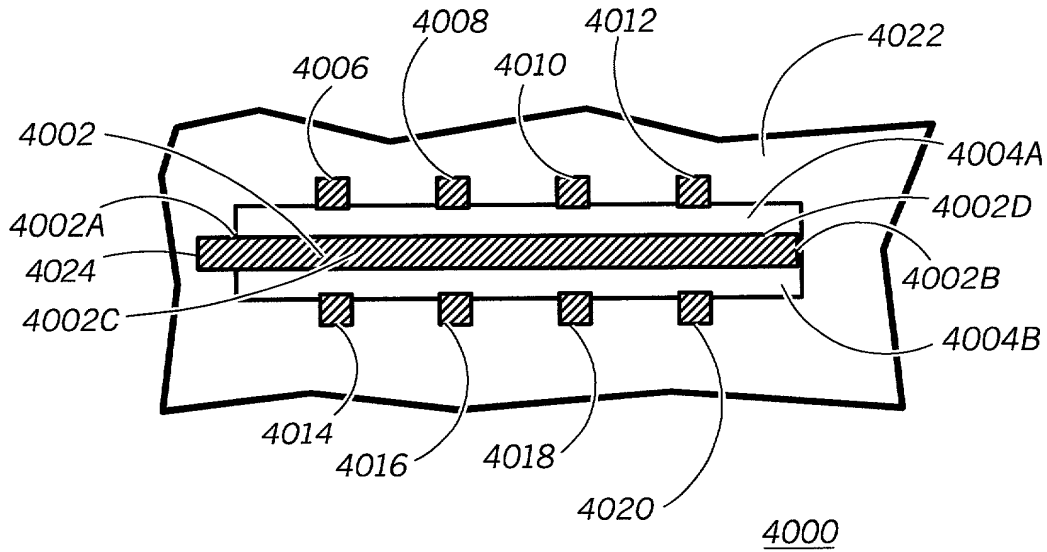


FIG. 40

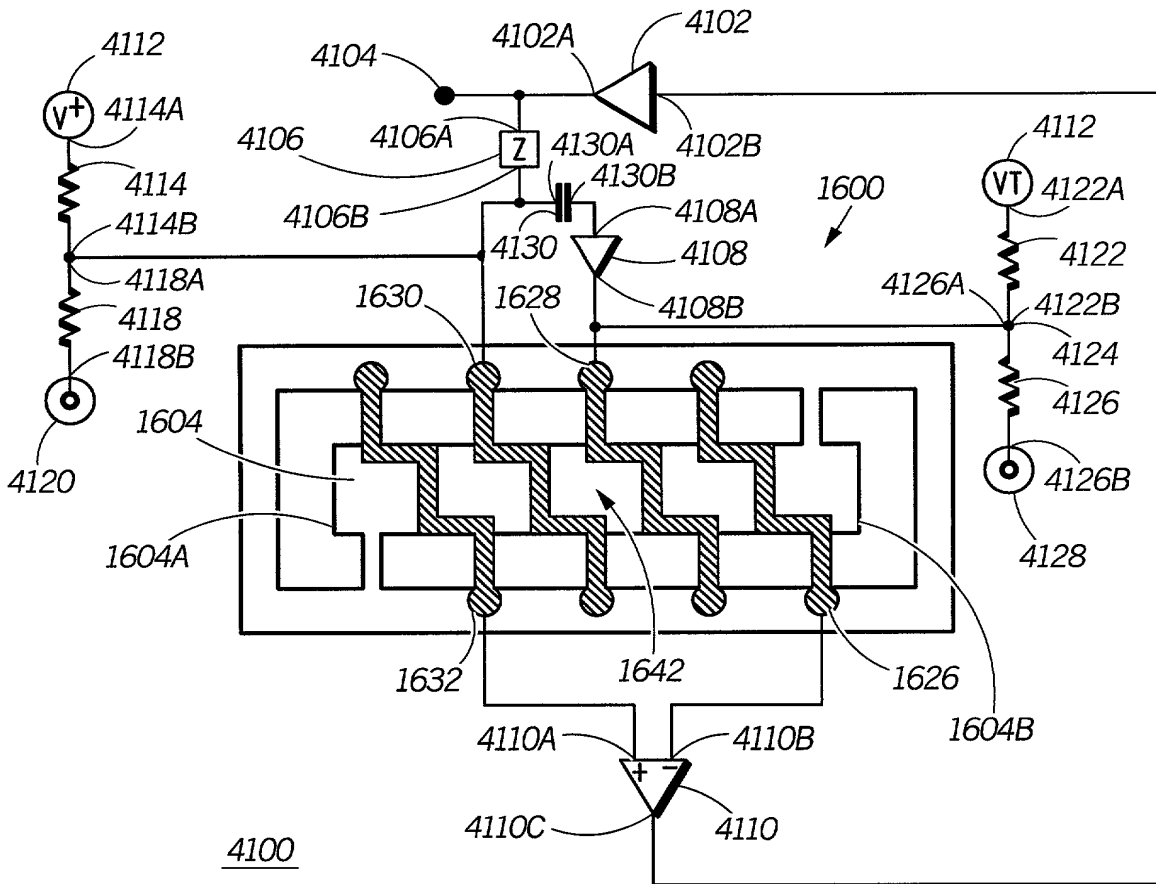


FIG. 41

FIG. 40

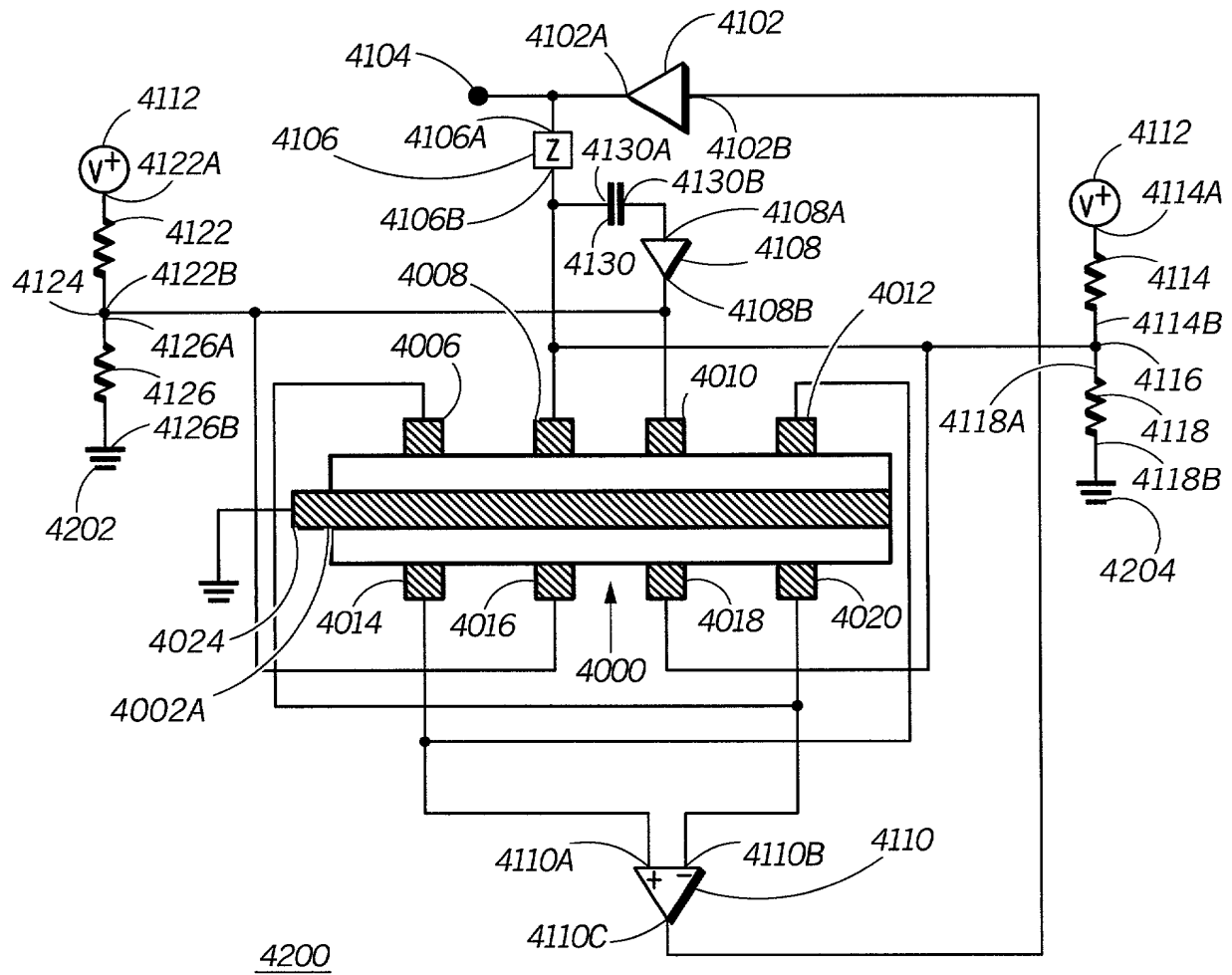


FIG. 42